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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

IN RE APPLICATION OF:

Kentarou TAMAKI, et al.

SERIAL NO: 10/550,534

GROUP: 2874

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EXAMINER: Michael J. STAHL

FOR: OPTICAL WAVEGUIDE CHIP AND OPTICAL COMPONENT COMPRISING
SAME

STATEMENT OF RELEVANCY

Reference AO on PTO form 1449 discloses a radiation-curable composition comprising (A) a specific hydrolyzable silane compound, its hydrolyzate, or its condensate, (B) a photoacid generator, and (C) a dehydrating agent.

Reference AP on PTO form 1449 discloses a composition for forming optical waveguides comprising (A) specific hydrolyzable silane compounds or its hydrolyzate, (B) a photoacid generator, and (C) a specific organic solvent. Reference AP also discloses an alkaline developing solution for developing thin layer which comprises the composition including the before-mentioned components (A)-(C) and which is partly cured in a specific pattern by radiation as described in paragraph [0095].

Reference AQ on PTO form 1449 discloses a method for manufacturing a silicon optical waveguide in which dry etching is used.

Reference AR on PTO form 1449 discloses a method for manufacturing an optical waveguide having an optical fiber guide in which reactive ion etching is used.

Reference AS on PTO form 1449 discloses a positive type radiosensitive composition comprising (A) a specific hydrolyzable silane compound, its hydrolyzate or its condensate, (B) an agent for generating acid by radiation, and (C) a basic compound.

Reference AT on PTO form 1449 discloses a wavelength filter 21 for being inserted and fixed in a groove 14 in a first optical fiber 11.

Reference AU on PTO form 1449 discloses an optical filter having an optical multilayer membrane.

Reference AW on PTO form 1449 discloses a photosensitive sol-gel material, which comprises a siloxane oligomer and photoacid generator, for forming optical waveguides by photolithography.